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AN - 2000-436422 [38]
 TI - Container for storage of chemical solution used in semiconductor manufacturing process, generates predetermined amount of particles when it is in contact with aqueous solution

AB - JP2000154238 NOVELTY - Aqueous solution such as acidic solution of pH 3, alkaline solution of pH 10 or hydrogen peroxide solution is filled inside a container (1) which is formed by blow molding of alicyclic structure containing polymer resin material. The amount of particles generated per 1 cm² of inner surface of container after maintaining the container containing aqueous solution under 23 deg. C for 24 hours, is less than 0.5 counts/ml.

- DETAILED DESCRIPTION - An INDEPENDENT CLAIM is also included for manufacture of container. The alicyclic structure containing polymeric resin material is volatilized below its glass transition temperature so that the volatile substance remaining in the resin material is 150 ppm or less. The resin material is then blow molded to obtain a container.

- USE - For storing chemical solution used in semiconductor manufacturing process (claimed) and for storing drugs and foodstuffs. As bumper for vehicles and as decorative panel.

- ADVANTAGE - The surface smoothness of the container is improved. The generation of particles during storage of chemical solution in the container is restrained, therefore the cleanliness of the chemical solution inside the container is maintained.

- DESCRIPTION OF DRAWING(S) - The figure shows the cross-sectional diagram of blow molded container.

- Container 1
 - (Dwg.1/1)

IW - CONTAINER STORAGE CHEMICAL SOLUTION
 SEMICONDUCTOR MANUFACTURE PROCESS GENERATE PREDETERMINED
 AMOUNT PARTICLE CONTACT AQUEOUS SOLUTION

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